

**Search Notes**

Application No.

10/633,093

Examiner

D. Rutledge

Applicant(s)

MORI, KENICHIRO

Art Unit

2851

**SEARCHED**

Class	Subclass	Date	Examiner
355	53,67,71, 77	9/18/2004	DR
355	68	9/18/2004	DR
250	205,548	9/18/2004	DR
430	311	9/18/2004	DR

**INTERFERENCE SEARCHED**

Class	Subclass	Date	Examiner
355	53, 67	9/20/2004	DR
355	71, 77	9/20/2004	DR
250	205, 548	9/20/2004	DR
430 311		9/20/2004	DR

**SEARCH NOTES  
(INCLUDING SEARCH STRATEGY)**

	DATE	EXMR
mask or reticle, desired or contact adj hole, second or auxiliary, pattern, best adj focus, highest adj resolution, none	9/18/2004	DR
un adj resolved, lamp or light or laser or source, distance, equation or condition or parameter or characteristic, hole adj	9/18/2004	DR
diameter, desired or contact adj hole, half adj pitch, auxiliary adj pattern, wavelength, numerical adj aperture	9/18/2004	DR
matrix, exposure, defocus\$3 or de adj focus\$3, location or position	9/18/2004	DR